

Access DB# 139655

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Amanda Walker Examiner #: 75663 Date: 12/2/04
Art Unit: 1752 Phone Number 301-270-1237 Serial Number: 10/806451
Mail Box and Bldg/Room Location: 12EM 9D64 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples of relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Bio Sheet Attached

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Please search for a comp of formula 2. Thank you

STAFF USE ONLY

	Type of Search	Vendors and cost where applicable
Searcher: <u>R. Fuller</u>	NA Sequence (#) _____	STN <u>✓</u>
Searcher Phone #: _____	AA Sequence (#) _____	Dialog _____
Searcher Location: _____	Structure (#) <u>6</u>	Questel/Orbit _____
Date Searcher Picked Up: _____	Bibliographic _____	Dr. Link _____
Date Completed: <u>12/20/04</u>	Litigation _____	Lexis/Nexis _____
Searcher Prep & Review Time: <u>30</u>	Fulltext _____	Sequence Systems _____
Clerical Prep Time: _____	Patent Family _____	WWW/Internet _____
Online Time: <u>40</u>	Other _____	Other (specify) _____

2 full searches



STIC Search Results Feedback Form

EIC17000

Questions about the scope or the results of the search? Contact the EIC searcher or contact:

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

- I am an examiner in Workgroup: Example: 1713
- Relevant prior art **found**, search results used as follows:

- ☐ 102 rejection
- ☐ 103 rejection
- ☐ Cited as being of interest.
- ☐ Helped examiner better understand the invention.
- ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature
(journal articles, conference proceedings, new product announcements etc.)

➤ Relevant prior art **not found**:

- ☐ Results verified the lack of relevant prior art (helped determine patentability).
- ☐ Results were not useful in determining patentability or understanding the invention.

Comments:

Drop off or send completed forms to EIC1700 REMSEN 4B28



=> FILE REG

FILE 'REGISTRY' ENTERED AT 12:44:02 ON 20 DEC 2004

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 19 DEC 2004 HIGHEST RN 799762-98-4

DICTIONARY FILE UPDATES: 19 DEC 2004 HIGHEST RN 799762-98-4

TSCA INFORMATION NOW CURRENT THROUGH MAY 21, 2004

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at:

<http://www.cas.org/ONLINE/DBSS/registryss.html>

=> FILE HCAPLUS

FILE 'HCAPLUS' ENTERED AT 12:44:06 ON 20 DEC 2004

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FILE COVERS 1907 - 20 Dec 2004 VOL 141 ISS 26

FILE LAST UPDATED: 19 Dec 2004 (20041219/ED)

This file contains CAS Registry Numbers for easy and accurate substance identification.

=> D QUE

L3

STR 1

8

G2

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O 7

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Ak—F

@5 6

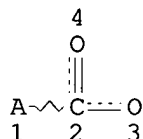
C—C—C—G1

1 2 3 4

VAR G1=5/F
VAR G2=H/A
NODE ATTRIBUTES:
DEFAULT MLEVEL IS ATOM
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 8

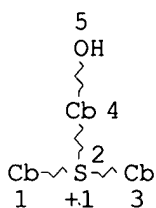
STEREO ATTRIBUTES: NONE
L4 STR 2



NODE ATTRIBUTES:
NSPEC IS RC AT 1
DEFAULT MLEVEL IS ATOM
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 4

STEREO ATTRIBUTES: NONE
L6 SCR 2043
L8 4365 SEA FILE=REGISTRY SSS FUL L3 AND L4 AND L6
L14 STR 3



NODE ATTRIBUTES:
CHARGE IS E+1 AT 2
DEFAULT MLEVEL IS ATOM
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 5

STEREO ATTRIBUTES: NONE
L16 SCR 2040
L18 SCR 1840
L20 149 SEA FILE=REGISTRY SSS FUL L14 AND L16 AND L18
L23 2162 SEA FILE=HCAPLUS ABB=ON L8
L24 139 SEA FILE=HCAPLUS ABB=ON L20
L25 4 SEA FILE=HCAPLUS ABB=ON L23 AND L24

A
4, 365 polymers from
structure 1 and 2

B
← 149 sulfonium compounds

4CA references
with A and B

=> D L25 ALL HITSTR 1-4

L25 ANSWER 1 OF 4 HCAPLUS COPYRIGHT 2004 ACS on STN
 AN 2004:796420 HCAPLUS
 DN 141:304288
 ED Entered STN: 30 Sep 2004
 TI Positive resist composition and method of forming resist pattern using the same
 IN Kodama, Kunihiro
 PA Fuji Photo Film Co., Ltd., Japan
 SO Eur. Pat. Appl., 46 pp.
 CODEN: EPXXDW
 DT Patent
 LA English
 IC ICM G03F007-004
 ICS G03F007-039
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38

Applicant

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1462858	A1	20040929	EP 2004-6536	20040318
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK				
	JP 2004287262	A2	20041014	JP 2003-81260	20030324
	US 2004197708	A1	20041007	<u>US 2004-806451</u>	20040323
PRAI	JP 2003-81260	A	20030324		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 1462858	ICM	G03F007-004
	ICS	G03F007-039
EP 1462858	ECLA	G03F007/004D; G03F007/004F; G03F007/039C1; G03F007/039C1S
JP 2004287262	FTERM	2H025/AA01; 2H025/AA02; 2H025/AA04; 2H025/AB16; 2H025/AC04; 2H025/AC08; 2H025/AD03; 2H025/BE07; 2H025/BE10; 2H025/BG00; 2H025/CB08; 2H025/CB14; 2H025/CB16; 2H025/CB41; 2H025/CB45; 2H025/FA17; 4J011/QA32; 4J011/SA87; 4J011/UA01; 4J011/VA01; 4J011/WA01
US 2004197708	ECLA	G03F007/004D; G03F007/004F; G03F007/039C1; G03F007/039C1S

AB A pos. resist composition comprising: (A) a fluorine atom-containing resin, wherein

the resin comprises at least one group that increases a solubility of the resin in an alkali developer by the action of an acid; and (B) a sulfonium salt compound having a cation moiety, wherein the cation moiety contains at least one hydroxy group, and the sulfonium salt compound generates an acid upon irradiation with one of an actinic ray and a radiation.

ST photoresist resist fluoropolymer sulfonium salt photoacid

IT Photoresists

Resists

(pos. resist composition from fluoropolymer and sulfonium salt photoacid)

IT 134993-70-7 240424-21-9 279218-75-6
 367522-51-8 370102-83-3 524699-48-7
 524699-56-7 524699-58-9 524699-59-0
 524699-60-3 524699-61-4 585573-40-6
 585573-50-8 607710-65-6 607710-74-7 669768-43-8

677354-71-1 732299-47-7 762274-01-1
 762275-99-0 764717-19-3 764717-20-6 764717-21-7
 764717-22-8 764717-23-9 764717-25-1 764717-26-2
 764717-28-4 764717-29-5 764717-30-8
 764717-32-0

RL: TEM (Technical or engineered material use); USES (Uses)
 (pos. resist composition from fluoropolymer and sulfonium salt photoacid)

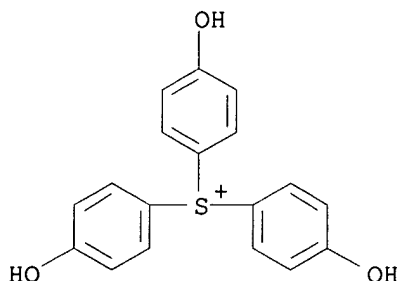
IT 134993-70-7 240424-21-9 279218-75-6
 370102-83-3 524699-48-7 524699-56-7
 524699-58-9 524699-59-0 524699-60-3
 524699-61-4 585573-50-8 607710-65-6
 677354-71-1 762274-01-1 762275-99-0
 764717-19-3 764717-26-2 764717-28-4
 764717-29-5 764717-30-8 764717-32-0

RL: TEM (Technical or engineered material use); USES (Uses)
 (pos. resist composition from fluoropolymer and sulfonium salt photoacid)

RN 134993-70-7 HCAPLUS
 CN Sulfonium, tris(4-hydroxyphenyl)-, salt with trifluoromethanesulfonic acid
 (1:1) (9CI) (CA INDEX NAME)

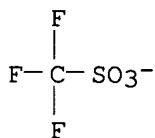
CM 1

CRN 88101-75-1
 CMF C18 H15 O3 S



CM 2

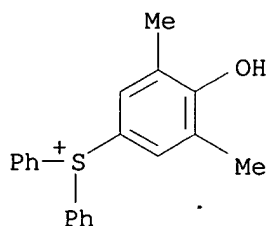
CRN 37181-39-8
 CMF C F3 O3 S



RN 240424-21-9 HCAPLUS
 CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)diphenyl-, salt with
 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX
 NAME)

CM 1

CRN 127279-85-0
CMF C20 H19 O S



CM 2

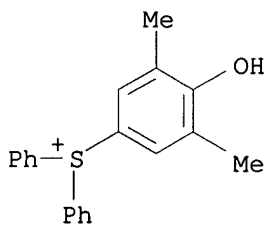
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}\text{O}_3\text{S}- (\text{CF}_2)_3-\text{CF}_3$

RN 279218-75-6 HCAPLUS
CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)diphenyl-, salt with
1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-1-octanesulfonic acid
(1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 127279-85-0
CMF C20 H19 O S



CM 2

CRN 45298-90-6
CMF C8 F17 O3 S

$^{-}\text{O}_3\text{S}- (\text{CF}_2)_7-\text{CF}_3$

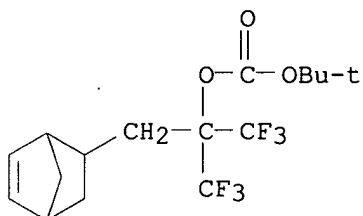
RN 370102-83-3 HCAPLUS
CN Carbonic acid, 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl ester, polymer with
 α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol

(9CI) (CA INDEX NAME)

CM 1

CRN 196314-63-3

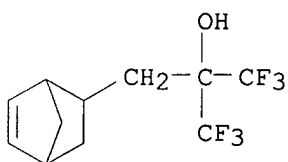
CMF C16 H20 F6 O3



CM 2

CRN 196314-61-1

CMF C11 H12 F6 O



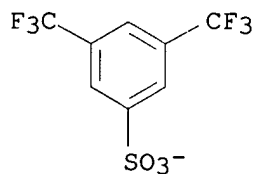
RN 524699-48-7 HCAPLUS

CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)diphenyl-, salt with
3,5-bis(trifluoromethyl)benzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 213740-84-2

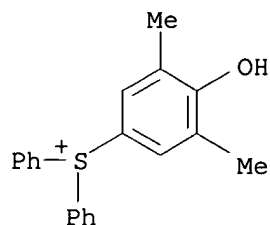
CMF C8 H3 F6 O3 S



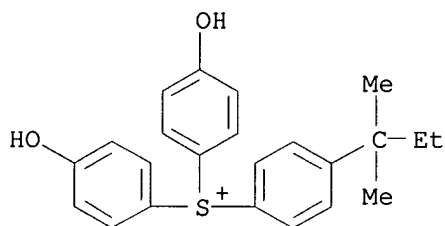
CM 2

CRN 127279-85-0

CMF C20 H19 O S



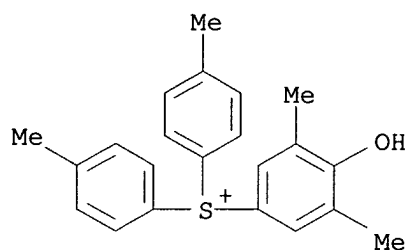
RN 524699-56-7 HCAPLUS
 CN Sulfonium, [4-(1,1-dimethylpropyl)phenyl]bis(4-hydroxyphenyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)
 CM 1
 CRN 508182-58-9
 CMF C23 H25 O2 S



CM 2
 CRN 45187-15-3
 CMF C4 F9 O3 S

$\text{-O}_3\text{S- (CF}_2)_3\text{-CF}_3$

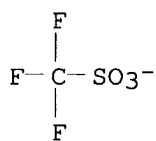
RN 524699-58-9 HCAPLUS
 CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)bis(4-methylphenyl)-, salt with trifluoromethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)
 CM 1
 CRN 478837-87-5
 CMF C22 H23 O S



CM 2

CRN 37181-39-8

CMF C F3 O3 S



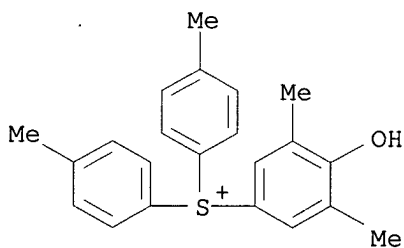
RN 524699-59-0 HCAPLUS

CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)bis(4-methylphenyl)-, salt with 1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptafluoro-1-octanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 478837-87-5

CMF C22 H23 O S



CM 2

CRN 45298-90-6

CMF C8 F17 O3 S

$^{-}O_3S-(CF_2)_7-CF_3$

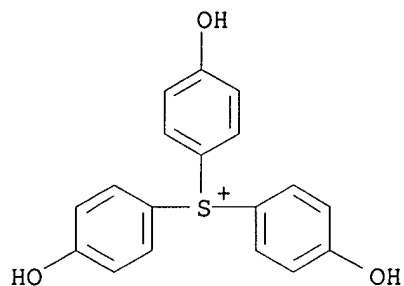
RN 524699-60-3 HCAPLUS

CN Sulfonium, tris(4-hydroxyphenyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 88101-75-1

CMF C18 H15 O3 S



CM 2

CRN 45187-15-3

CMF C4 F9 O3 S

$^{-}O_3S^{-} (CF_2)_3^{-}CF_3$

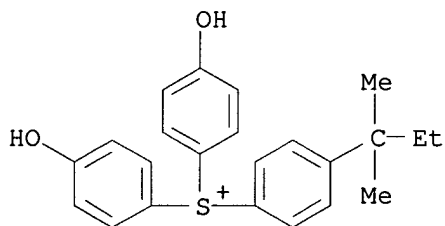
RN 524699-61-4 HCAPLUS

CN Sulfonium, [4-(1,1-dimethylpropyl)phenyl]bis(4-hydroxyphenyl)-, salt with 1,1,2,2-tetrafluoro-2-(pentafluoroethoxy)ethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 508182-58-9

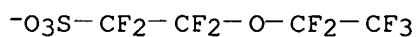
CMF C23 H25 O2 S



CM 2

CRN 220689-13-4

CMF C4 F9 O4 S



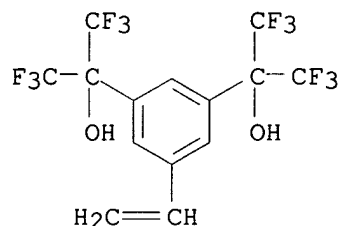
RN 585573-50-8 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 5-ethenyl- $\alpha,\alpha,\alpha',\alpha'$ -tetrakis(trifluoromethyl)-1,3-benzenedimethanol (9CI) (CA INDEX NAME)

CM 1

CRN 568587-26-8

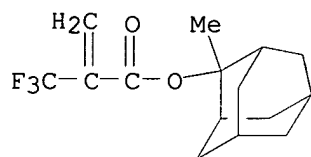
CMF C14 H8 F12 O2



CM 2

CRN 188739-86-8

CMF C15 H19 F3 O2



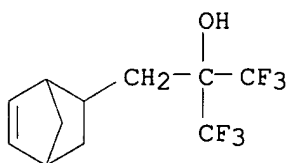
RN 607710-65-6 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 196314-61-1

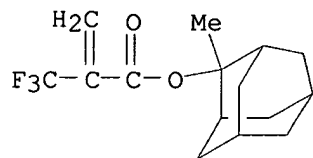
CMF C11 H12 F6 O



CM 2

CRN 188739-86-8

CMF C15 H19 F3 O2



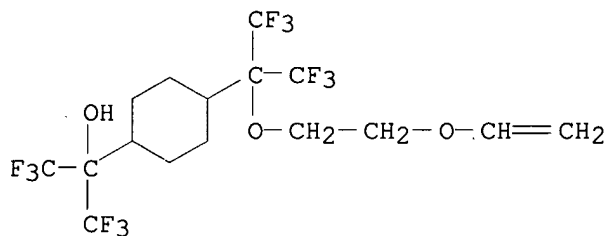
RN 677354-71-1 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 4-[1-[2-(ethenyloxy)ethoxy]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]- α,α -bis(trifluoromethyl)cyclohexanemethanol and 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 654076-29-6

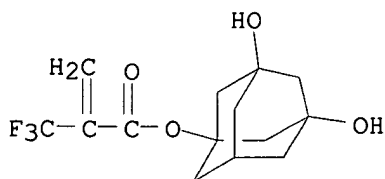
CMF C16 H18 F12 O3



CM 2

CRN 521913-16-6

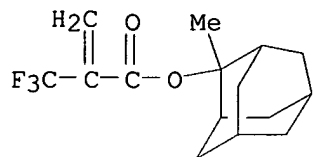
CMF C14 H17 F3 O4



CM 3

CRN 188739-86-8

CMF C15 H19 F3 O2



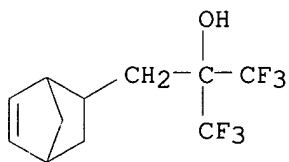
RN 762274-01-1 HCAPLUS

CN 2-Propenoic acid, 1,1-dimethylethyl ester, polymer with
 α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol and
 tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 196314-61-1

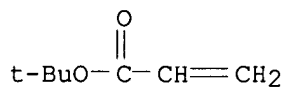
CMF C11 H12 F6 O



CM 2

CRN 1663-39-4

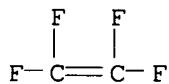
CMF C7 H12 O2



CM 3

CRN 116-14-3

CMF C2 F4



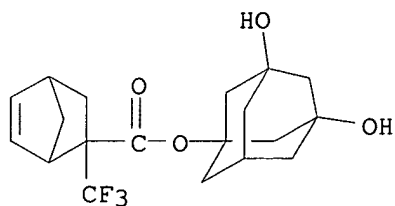
RN 762275-99-0 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(trifluoromethyl)-,
 3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with
 α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol and
 1,1-dimethylethyl 5(or 6)-(ethenyloxy)-2-(trifluoromethyl)bicyclo[2.2.1]he
 ptane-2-carboxylate (9CI) (CA INDEX NAME)

CM 1

CRN 731861-90-8

CMF C19 H23 F3 O4

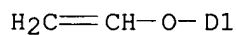
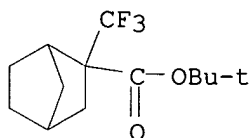


CM 2

CRN 679804-76-3

CMF C15 H21 F3 O3

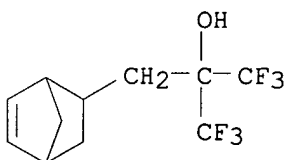
CCI IDS



CM 3

CRN 196314-61-1

CMF C11 H12 F6 O



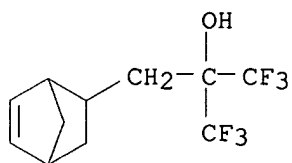
RN 764717-19-3 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, butyl ester, polymer with
 α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol
 (9CI) (CA INDEX NAME)

CM 1

CRN 196314-61-1

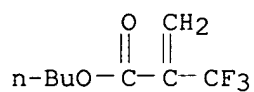
CMF C11 H12 F6 O



CM 2

CRN 105935-22-6

CMF C8 H11 F3 O2



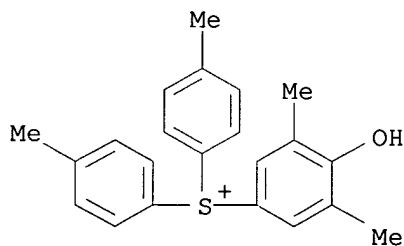
RN 764717-26-2 HCAPLUS

CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)bis(4-methylphenyl)-, salt with 1,1,1-trifluoro-N-[(trifluoromethyl)sulfonyl]methanesulfonamide (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 478837-87-5

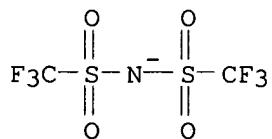
CMF C22 H23 O S



CM 2

CRN 98837-98-0

CMF C2 F6 N O4 S2



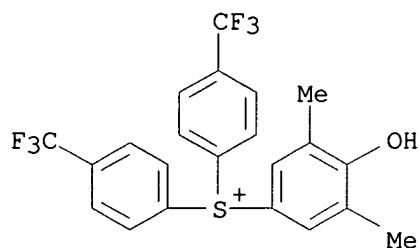
RN 764717-28-4 HCAPLUS

CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)bis[4-(trifluoromethyl)phenyl]-, salt with 3,5-bis(trifluoromethyl)benzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 764717-27-3

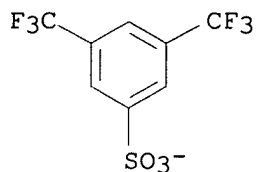
CMF C22 H17 F6 O S



CM 2

CRN 213740-84-2

CMF C8 H3 F6 O3 S



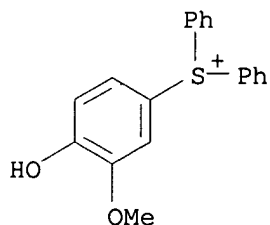
RN 764717-29-5 HCAPLUS

CN Sulfonium, (4-hydroxy-3-methoxyphenyl)diphenyl-, salt with 3,5-bis(trifluoromethyl)benzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

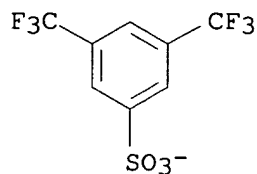
CRN 528605-47-2

CMF C19 H17 O2 S



CM 2

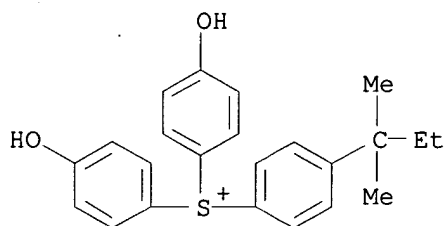
CRN 213740-84-2
CMF C8 H3 F6 O3 S



RN 764717-30-8 HCAPLUS
CN Sulfonium, [4-(1,1-dimethylpropyl)phenyl]bis(4-hydroxyphenyl)-, salt with pentafluorobenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

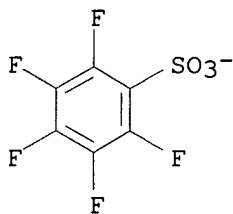
CM 1

CRN 508182-58-9
CMF C23 H25 O2 S



CM 2

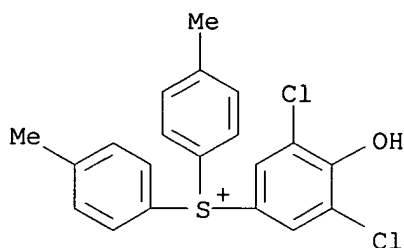
CRN 46377-88-2
CMF C6 F5 O3 S



RN 764717-32-0 HCAPLUS
CN Sulfonium, (3,5-dichloro-4-hydroxyphenyl)bis(4-methylphenyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 764717-31-9
CMF C20 H17 Cl2 O S



CM 2

CRN 45187-15-3

CMF C4 F9 O3 S

-O₃S- (CF₂)₃-CF₃

L25 ANSWER 2 OF 4 HCAPLUS COPYRIGHT 2004 ACS on STN
 AN 2003:943682 HCAPLUS
 DN 140:10635
 ED Entered STN: 04 Dec 2003
 TI Positive-working photoresist composition
 IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya
 PA Fuji Photo Film Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 56 pp.
 CODEN: JKXXAF

DT Patent

LA Japanese

IC ICM G03F007-039

ICS C08F012-14; C08F014-18; C08F032-00; G03F007-004; H01L021-027

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other
 Reprographic Processes)
 Section cross-reference(s): 35

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003345022	A2	20031203	JP 2002-152581	20020527
PRAI	JP 2002-152581		20020527		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2003345022	ICM	G03F007-039
	ICS	C08F012-14; C08F014-18; C08F032-00; G03F007-004; H01L021-027

AB The title composition contains fluorine-containing resin, which is solubilizable in an alkali developer by reacting with an acid, and an actinic ray- or radiation sensitive acid generator, wherein the resin has a fluorine substituent in the main and/or the side chain and wherein the acid generator generates a sulfonic acid having a fluorine-substituted aromatic ring. The composition shows good transparency towards 160 nm light and little dependency on the development duration.

ST pos photoresist compn resin acid generator

IT Light-sensitive materials
Positive photoresists
(pos.-working photoresist composition)

IT 1643-69-2, 3-(Trifluoromethyl)benzenesulfonic acid 3744-08-9,
Triphenylsulfonium iodide
RL: RCT (Reactant); RACT (Reactant or reagent)
(acid-generator in pos.-working photoresist composition)

IT 270563-92-3P 398457-16-4P 405893-15-4P 474510-79-7P 477327-74-5P
508182-57-8P 564472-78-2P 628709-14-8P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(acid-generator in pos.-working photoresist composition)

IT 430437-13-1P 430437-18-6P **430437-33-5P** **487048-93-1P**
524952-72-5P **597581-39-0P** 628709-07-9P 628709-08-0P
628709-09-1P **628709-10-4P** 628709-11-5P **628709-12-6P**
628709-13-7P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(resin in pos.-working photoresist composition)

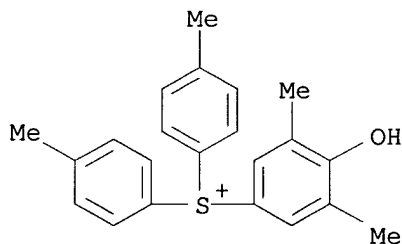
IT **508182-57-8P**
RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(acid-generator in pos.-working photoresist composition)

RN 508182-57-8 HCAPLUS

CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)bis(4-methylphenyl)-, salt with
3,5-bis(trifluoromethyl)benzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

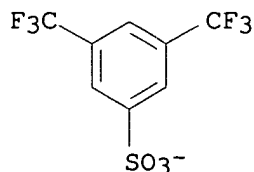
CM 1

CRN 478837-87-5
CMF C22 H23 O S



CM 2

CRN 213740-84-2
CMF C8 H3 F6 O3 S



IT 430437-33-5P 487048-93-1P 597581-39-0P
628709-10-4P 628709-12-6P 628709-13-7P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(resin in pos.-working photoresist composition)

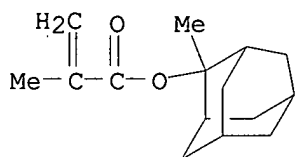
RN 430437-33-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 177080-67-0

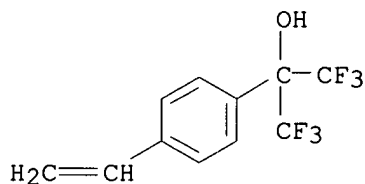
CMF C15 H22 O2



CM 2

CRN 2386-82-5

CMF C11 H8 F6 O



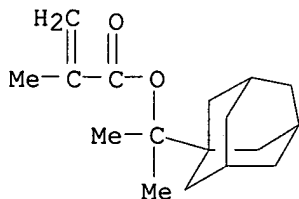
RN 487048-93-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-methyl-1-tricyclo[3.3.1.1^{3,7}]dec-1-ylethyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 279218-76-7

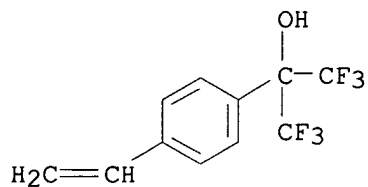
CMF C17 H26 O2



CM 2

CRN 2386-82-5

CMF C11 H8 F6 O



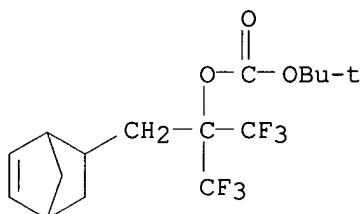
RN 597581-39-0 HCAPLUS

CN Carbonic acid, 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol, 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 196314-63-3

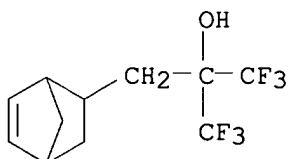
CMF C16 H20 F6 O3



CM 2

CRN 196314-61-1

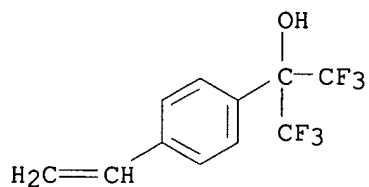
CMF C11 H12 F6 O



CM 3

CRN 2386-82-5

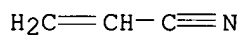
CMF C11 H8 F6 O



CM 4

CRN 107-13-1

CMF C3 H3 N



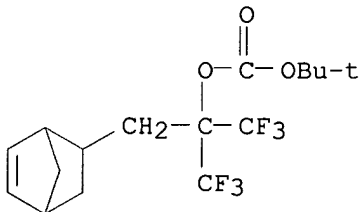
RN 628709-10-4 HCAPLUS

CN Carbonic acid, 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 196314-63-3

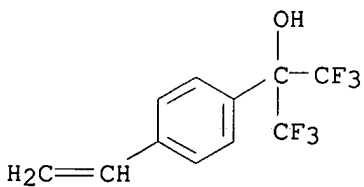
CMF C16 H20 F6 O3



CM 2

CRN 2386-82-5

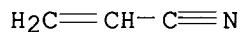
CMF C11 H8 F6 O



CM 3

CRN 107-13-1

CMF C3 H3 N



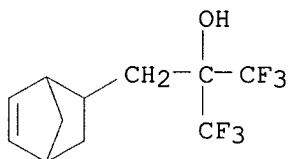
RN 628709-12-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1,1-dimethylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol and tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 196314-61-1

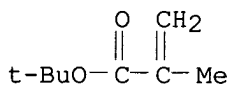
CMF C11 H12 F6 O



CM 2

CRN 585-07-9

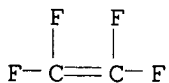
CMF C8 H14 O2



CM 3

CRN 116-14-3

CMF C2 F4



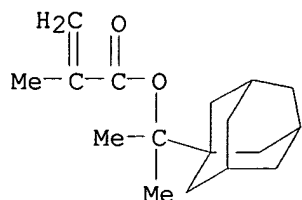
RN 628709-13-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-methyl-1-tricyclo[3.3.1.1^{3,7}]dec-1-ylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

CM 1

CRN 279218-76-7

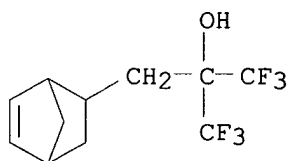
CMF C17 H26 O2



CM 2

CRN 196314-61-1

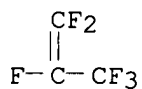
CMF C11 H12 F6 O



CM 3

CRN 116-15-4

CMF C3 F6



L25 ANSWER 3 OF 4 HCAPLUS COPYRIGHT 2004 ACS on STN
AN 2003:868612 HCAPLUS
DN 139:371875
ED Entered STN: 06 Nov 2003
TI Positive-working resist composition for vacuum-UV exposure
IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 25 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-039
ICS C08F020-30; G03F007-004; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 35, 37, 38

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003316005	A2	20031106	JP 2002-122269	20020424
PRAI	JP 2002-122269		20020424		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2003316005	ICM	G03F007-039
	ICS	C08F020-30; G03F007-004; H01L021-027

GI

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

AB The pos.-working resist composition comprises (a) a photoacid represented by I or II (R1a-27a = H, alkyl, alkoxy, etc.; and X- = anion), (b) a resin which increases its solubility in an alkali developer upon contact with an acid, and (c) a solvent. The composition further comprises a surfactant containing

Si and/or F. The composition further comprises an organic base compound. The pos.-working resist composition exhibited a suppressed outgassing.

ST pos working resist photoresist compn vacuum UV exposure; photoacid resin surfactant

IT Photoresists

Resists

Surfactants

(pos.-working resist composition for vacuum-UV exposure)

IT Polysiloxanes, uses

RL: TEM (Technical or engineered material use); USES (Uses)

(surfactant; pos.-working resist composition for vacuum-UV exposure)

IT 60-80-0, Antipyrine 75-59-2, Tetramethylammonium hydroxide 122-20-3, Triisopropanolamine 484-47-9 1116-76-3, Trioctylamine 3001-72-7, 1,5-Diazabicyclo[4.3.0]-5-nonene 24544-04-5, 2,6-Diisopropylaniline 41556-26-7, Bis(1,2,2,6,6-pentamethyl-4-piperidyl sebacate

RL: TEM (Technical or engineered material use); USES (Uses)

(base compound; pos.-working resist composition for vacuum-UV exposure)

IT 297742-41-7 376600-59-8 405284-04-0 405284-05-1 405284-06-2

620172-21-6 620172-23-8 620172-25-0 620172-26-1

620172-27-2 620172-28-3 620172-29-4 620172-30-7 620172-31-8

620172-32-9 620172-33-0 620172-34-1 620172-35-2

620172-36-3 620172-38-5 620172-40-9

RL: TEM (Technical or engineered material use); USES (Uses)

(photoacid; pos.-working resist composition for vacuum-UV exposure)

IT 370866-39-0P

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(pos.-working resist composition for vacuum-UV exposure)

IT 143336-94-1 370102-83-3 406702-00-9

430437-18-6 459418-30-5 607710-65-6 607710-66-7

607710-67-8 607710-68-9 607710-69-0 607710-70-3

607710-71-4 607710-72-5 607710-73-6

607710-76-9 607710-77-0 607710-78-1

610300-97-5 610300-98-6 610301-00-3

610301-01-4 610301-03-6

RL: PRP (Properties); TEM (Technical or engineered material use); USES

(Uses)

(pos.-working resist composition for vacuum-UV exposure)

IT 9016-45-9, Polyoxyethylenenonylphenyl ether 137462-24-9, Megafac F176
216679-67-3, Megafac R08

RL: TEM (Technical or engineered material use); USES (Uses)

(surfactant; pos.-working resist composition for vacuum-UV exposure)

IT 620172-23-8 620172-32-9

RL: TEM (Technical or engineered material use); USES (Uses)

(photoacid; pos.-working resist composition for vacuum-UV exposure)

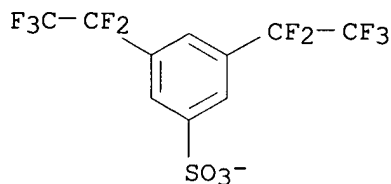
RN 620172-23-8 HCAPLUS

CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)diphenyl-, salt with
3,5-bis(pentafluoroethyl)benzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 620172-22-7

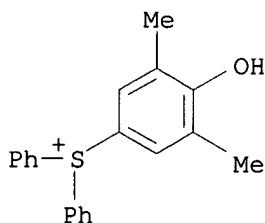
CMF C10 H3 F10 O3 S



CM 2

CRN 127279-85-0

CMF C20 H19 O S



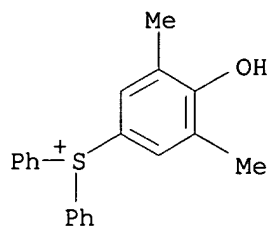
RN 620172-32-9 HCAPLUS

CN Sulfonium, (4-hydroxy-3,5-dimethylphenyl)diphenyl-, salt with
heptafluorobutanoic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

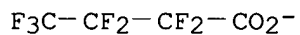
CRN 127279-85-0

CMF C20 H19 O S



CM 2

CRN 45048-62-2
CMF C4 F7 O2



IT **370866-39-0P**

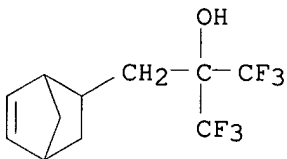
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos.-working resist composition for vacuum-UV exposure)

RN 370866-39-0 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

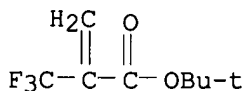
CM 1

CRN 196314-61-1
CMF C11 H12 F6 O



CM 2

CRN 105935-24-8
CMF C8 H11 F3 O2



IT **143336-94-1 370102-83-3 406702-00-9**
607710-65-6 607710-70-3 607710-71-4
607710-72-5 607710-73-6 607710-76-9

607710-77-0 607710-78-1 610300-97-5
610300-98-6 610301-00-3 610301-01-4
610301-03-6

RL: PRP (Properties); TEM (Technical or engineered material use); USES
(Uses)

(pos.-working resist composition for vacuum-UV exposure)

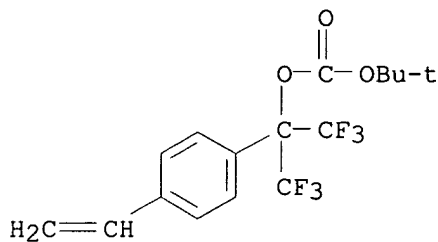
RN 143336-94-1 HCAPLUS

CN Carbonic acid, 1,1-dimethylethyl 1-(4-ethenylphenyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 143336-93-0

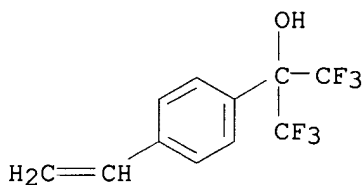
CMF C16 H16 F6 O3



CM 2

CRN 2386-82-5

CMF C11 H8 F6 O



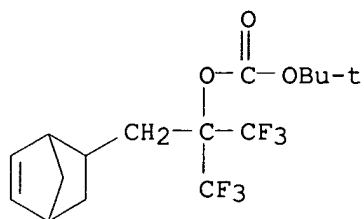
RN 370102-83-3 HCAPLUS

CN Carbonic acid, 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 196314-63-3

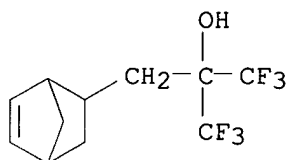
CMF C16 H20 F6 O3



CM 2

CRN 196314-61-1

CMF C11 H12 F6 O



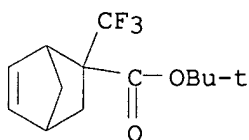
RN 406702-00-9 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 365568-55-4

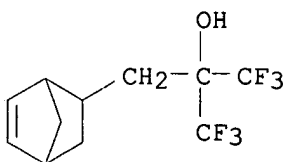
CMF C13 H17 F3 O2



CM 2

CRN 196314-61-1

CMF C11 H12 F6 O



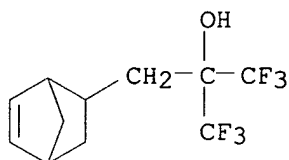
RN 607710-65-6 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 196314-61-1

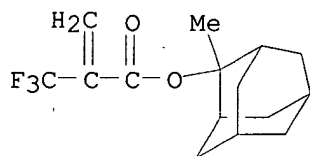
CMF C11 H12 F6 O



CM 2

CRN 188739-86-8

CMF C15 H19 F3 O2



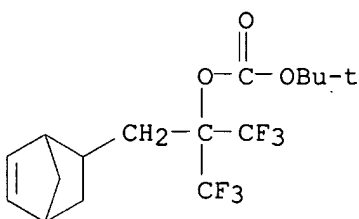
RN 607710-70-3 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, tricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl carbonate (9CI) (CA INDEX NAME)

CM 1

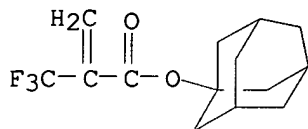
CRN 196314-63-3

CMF C16 H20 F6 O3



CM 2

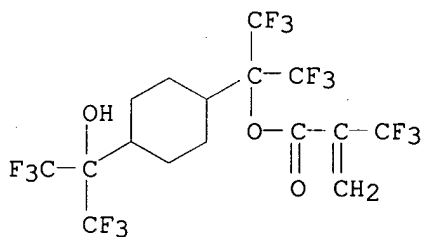
CRN 188739-82-4
CMF C14 H17 F3 O2



RN 607710-71-4 HCAPLUS
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl ester, polymer with 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl carbonate (9CI) (CA INDEX NAME)

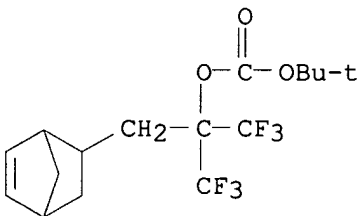
CM 1

CRN 479072-83-8
CMF C16 H13 F15 O3



CM 2

CRN 196314-63-3
CMF C16 H20 F6 O3

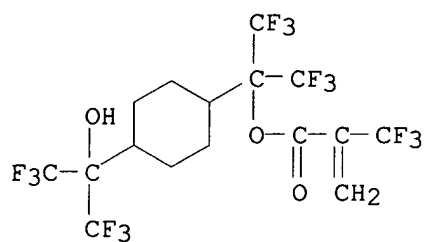


RN 607710-72-5 HCAPLUS
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 479072-83-8

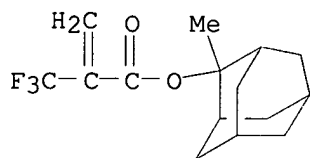
CMF C16 H13 F15 O3



CM 2

CRN 188739-86-8

CMF C15 H19 F3 O2



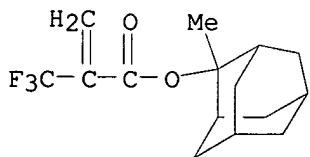
RN 607710-73-6 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 188739-86-8

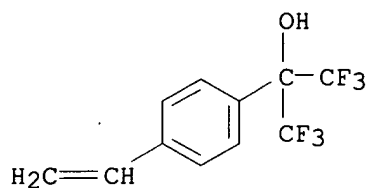
CMF C15 H19 F3 O2



CM 2

CRN 2386-82-5

CMF C11 H8 F6 O



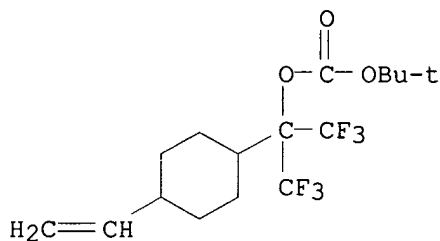
RN 607710-76-9 HCAPLUS

CN Carbonic acid, 1,1-dimethylethyl 1-(4-ethenylcyclohexyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)cyclohexanemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 607710-75-8

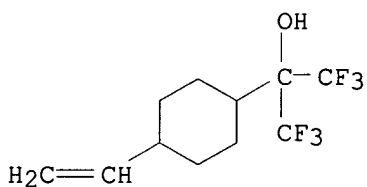
CMF C16 H22 F6 O3



CM 2

CRN 607710-74-7

CMF C11 H14 F6 O



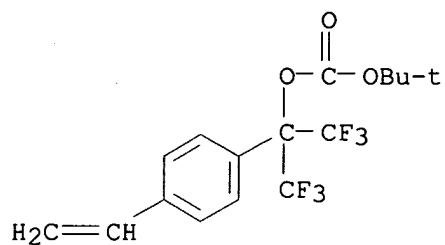
RN 607710-77-0 HCAPLUS

CN Carbonic acid, 1,1-dimethylethyl 1-(4-ethenylphenyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene and 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 143336-93-0

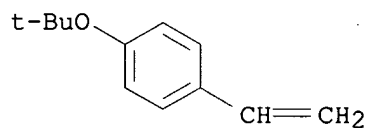
CMF C16 H16 F6 O3



CM 2

CRN 95418-58-9

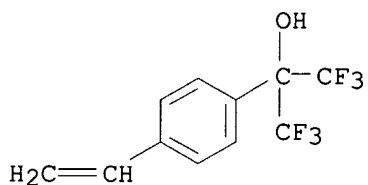
CMF C12 H16 O



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



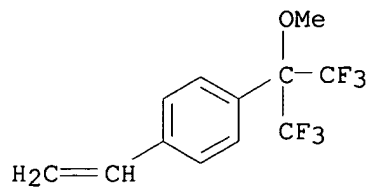
RN 607710-78-1 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 1-ethenyl-4-[2,2,2-trifluoro-1-methoxy-1-(trifluoromethyl)ethyl]benzene (9CI) (CA INDEX NAME)

CM 1

CRN 483348-89-6

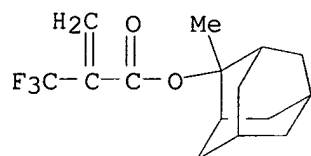
CMF C12 H10 F6 O



CM 2

CRN 188739-86-8

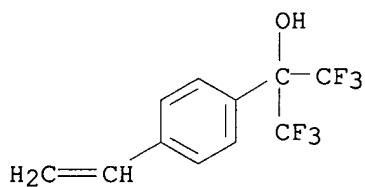
CMF C15 H19 F3 O2



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



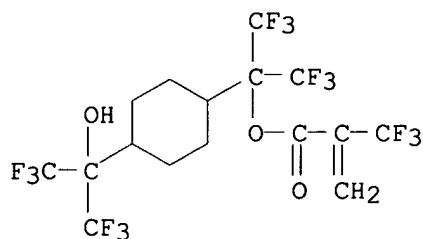
RN 610300-97-5 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl ester, polymer with 5-[2-(ethoxymethoxy)-3,3,3-trifluoro-2-(trifluoromethyl)propyl]bicyclo[2.2.1]hept-2-ene (9CI) (CA INDEX NAME)

CM 1

CRN 479072-83-8

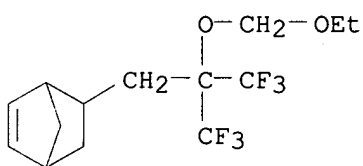
CMF C16 H13 F15 O3



CM 2

CRN 328114-61-0

CMF C14 H18 F6 O2



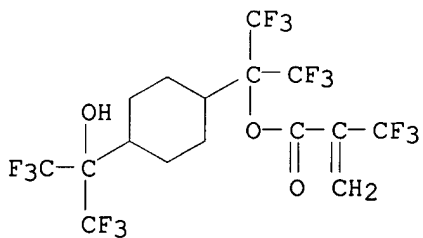
RN 610300-98-6 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 479072-83-8

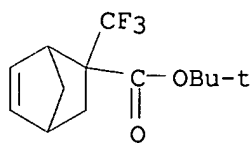
CMF C16 H13 F15 O3



CM 2

CRN 365568-55-4

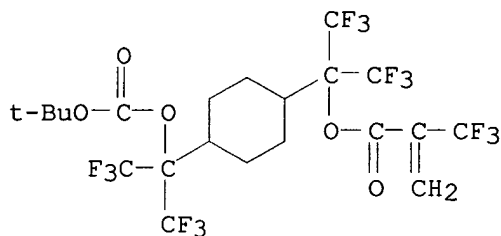
CMF C13 H17 F3 O2



RN 610301-00-3 HCAPLUS
 CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1-[4-[1-[(1,1-dimethylethoxy)carbonyl]oxy]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]cyclohexyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with tricyclo[3.3.1.13,7]dec-1-yl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

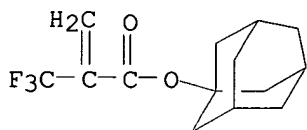
CM 1

CRN 610300-99-7
 CMF C21 H21 F15 O5



CM 2

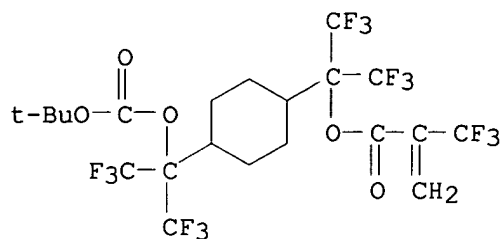
CRN 188739-82-4
 CMF C14 H17 F3 O2



RN 610301-01-4 HCAPLUS
 CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1-[4-[1-[(1,1-dimethylethoxy)carbonyl]oxy]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]cyclohexyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

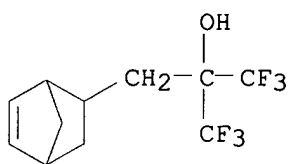
CRN 610300-99-7
 CMF C21 H21 F15 O5



CM 2

CRN 196314-61-1

CMF C11 H12 F6 O



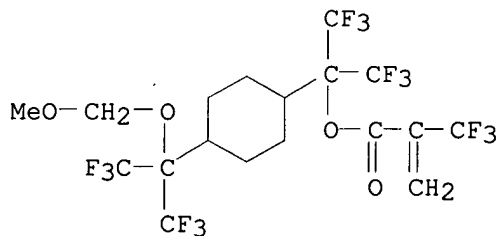
RN 610301-03-6 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(trifluoromethyl)-, methyl ester, polymer with 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-(methoxymethoxy)-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 610301-02-5

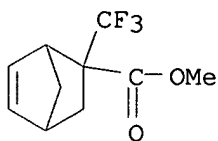
CMF C18 H17 F15 O4



CM 2

CRN 597581-42-5

CMF C10 H11 F3 O2



L25 ANSWER 4 OF 4 HCAPLUS COPYRIGHT 2004 ACS on STN
 AN 2003:853325 HCAPLUS
 DN 139:356048
 ED Entered STN: 31 Oct 2003
 TI Positive-working photoresist composition
 IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya
 PA Fuji Photo Film Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 36 pp.
 CODEN: JKXXAF

DT Patent
 LA Japanese

IC ICM G03F007-039
 ICS C08F012-14; C08F016-22; C08F020-22; C08F020-26; C08F032-04;
 G03F007-004; H01L021-027

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other
 Reprographic Processes)

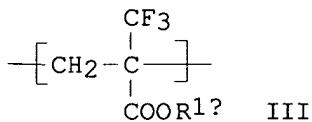
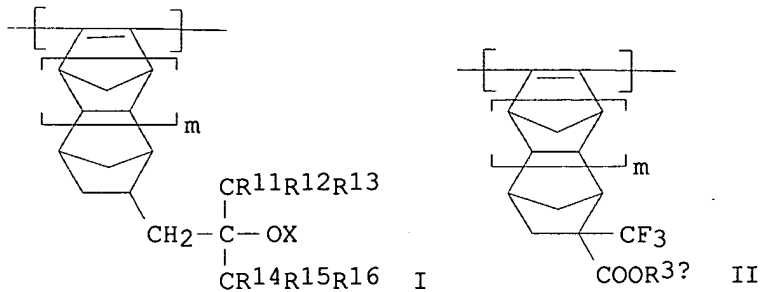
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003307850	A2	20031031	JP 2002-112257	20020415
PRAI JP 2002-112257		20020415		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2003307850	ICM	G03F007-039
	ICS	C08F012-14; C08F016-22; C08F020-22; C08F020-26; C08F032-04; G03F007-004; H01L021-027

OS MARPAT 139:356048
 GI



AB The title composition contains a photoacid generator, a resin increasing the solubility in an alkali developer by an acid, and a solvent, wherein the acid generator has general structure (R1)(R2)(R3)S+ X- or R4-I+-R5 X- (R1-5 = aliphatic hydrocarbon, aromatic hydrocarbon; X = anion) and wherein the resin contains at least one of repeating unit chosen from I, II, (m = 0,1; X = H, acid-sensitive group; R11-16 = H, F, fluoroalkyl; R3a = H, acid-sensitive group), [-CH2-C(CF3)(CO2R14)-] (R4a = H, acid-sensitive group), etc. The composition is suitable for exposure of ≤ 160 nm light and provides photoresist of good line-edge roughness and little residual layer after the development.

ST pos working photoresist compn

IT Positive photoresists

(pos.-working photoresist composition)

IT	393110-05-9	460731-17-3	460731-18-4	460731-19-5	460731-20-8
	460731-21-9	460731-23-1	460731-25-3	460731-26-4	460731-27-5
	460731-28-6	460731-29-7	460731-32-2	476315-57-8	476315-59-0
	476315-60-3	476315-64-7	476315-65-8	476315-66-9	476315-67-0
	618097-09-9	618097-11-3	618097-12-4		

RL: TEM (Technical or engineered material use); USES (Uses)
(acid generator in composition)

IT **143336-94-1 370102-83-3 370866-39-0**

406702-00-9 430437-18-6 459418-30-5 **607710-65-6**

607710-66-7 607710-67-8 607710-68-9 607710-69-0 **607710-70-3**

607710-71-4 607710-72-5 607710-73-6

607710-76-9 607710-77-0 607710-78-1

610300-97-5 610300-98-6 610301-00-3

610301-03-6

RL: TEM (Technical or engineered material use); USES (Uses)
(resin in composition)

IT 96-48-0, γ -Butyrolactone 105-37-3 141-78-6, Ethyl acetate, uses
1320-67-8, Propylene glycol monomethyl ether 84540-57-8, Propylene
glycol monomethyl ether acetate

RL: NUU (Other use, unclassified); USES (Uses)
(solvent in composition)

IT **618097-11-3**

RL: TEM (Technical or engineered material use); USES (Uses)
(acid generator in composition)

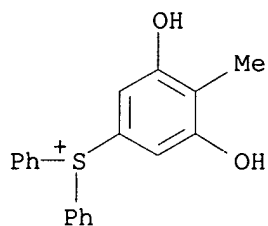
RN 618097-11-3 HCAPLUS

CN Sulfonium, (3,5-dihydroxy-4-methylphenyl)diphenyl-, salt with
1,1'-[[[(trifluoromethyl)sulfonyl]methylene]bis(sulfonyl)]bis[1,1,2,2,3,3,
4,4,4-nonafluorobutane] (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 618097-10-2

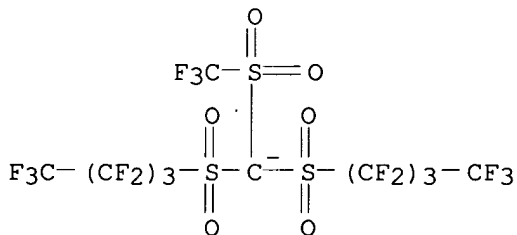
CMF C19 H17 O2 S



CM 2

CRN 476315-63-6

CMF C10 F21 O6 S3



IT 143336-94-1 370102-83-3 370866-39-0
406702-00-9 607710-65-6 607710-70-3
607710-71-4 607710-72-5 607710-73-6
607710-76-9 607710-77-0 607710-78-1
610300-97-5 610300-98-6 610301-00-3
610301-03-6

RL: TEM (Technical or engineered material use); USES (Uses)
(resin in composition)

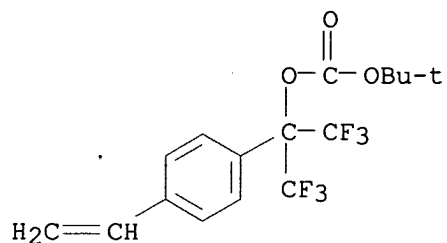
RN 143336-94-1 HCAPLUS

CN Carbonic acid, 1,1-dimethylethyl 1-(4-ethenylphenyl)-2,2,2-trifluoro-1-
(trifluoromethyl)ethyl ester, polymer with 4-ethenyl- α,α -
bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 143336-93-0

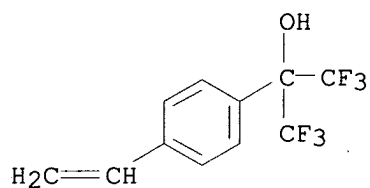
CMF C16 H16 F6 O3



CM 2

CRN 2386-82-5

CMF C11 H8 F6 O



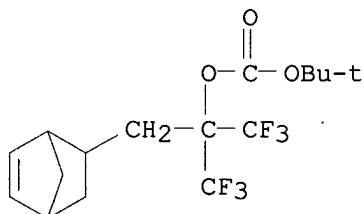
RN 370102-83-3 HCAPLUS

CN Carbonic acid, 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 196314-63-3

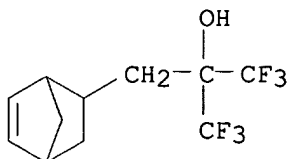
CMF C16 H20 F6 O3



CM 2

CRN 196314-61-1

CMF C11 H12 F6 O



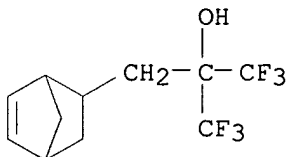
RN 370866-39-0 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 196314-61-1

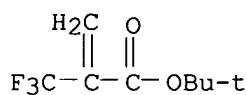
CMF C11 H12 F6 O



CM 2

CRN 105935-24-8

CMF C8 H11 F3 O2



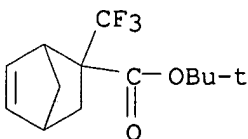
RN 406702-00-9 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 365568-55-4

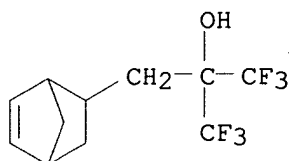
CMF C13 H17 F3 O2



CM 2

CRN 196314-61-1

CMF C11 H12 F6 O



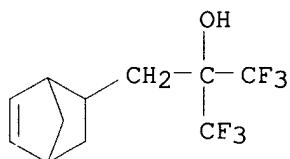
RN 607710-65-6 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with α,α -bis(trifluoromethyl)bicyclo[2.2.1]hept-5-ene-2-ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 196314-61-1

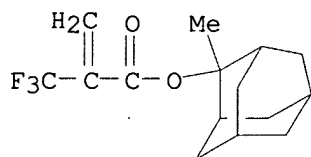
CMF C11 H12 F6 O



CM 2

CRN 188739-86-8

CMF C15 H19 F3 O2



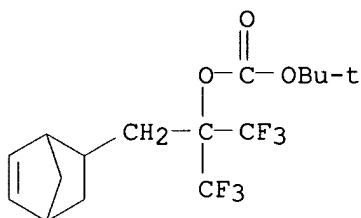
RN 607710-70-3 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, tricyclo[3.3.1.13,7]dec-1-yl ester, polymer with 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl carbonate (9CI) (CA INDEX NAME)

CM 1

CRN 196314-63-3

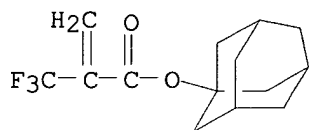
CMF C16 H20 F6 O3



CM 2

CRN 188739-82-4

CMF C14 H17 F3 O2



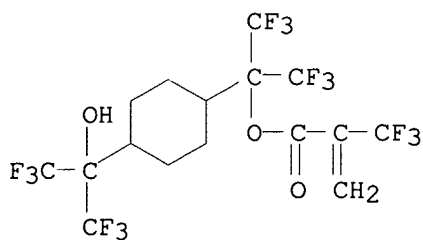
RN 607710-71-4 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl ester, polymer with 1-(bicyclo[2.2.1]hept-5-en-2-ylmethyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl 1,1-dimethylethyl carbonate (9CI) (CA INDEX NAME)

CM 1

CRN 479072-83-8

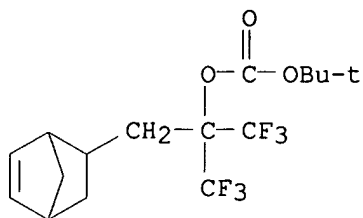
CMF C16 H13 F15 O3



CM 2

CRN 196314-63-3

CMF C16 H20 F6 O3

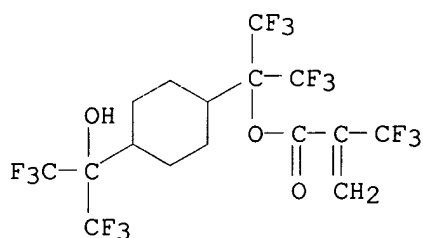


RN 607710-72-5 HCAPLUS
 CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 479072-83-8

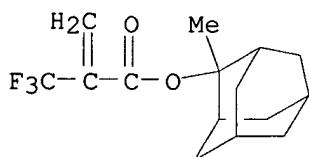
CMF C16 H13 F15 O3



CM 2

CRN 188739-86-8

CMF C15 H19 F3 O2

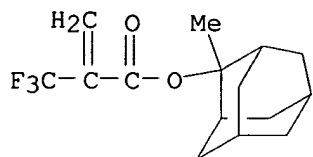


RN 607710-73-6 HCAPLUS
 CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 188739-86-8

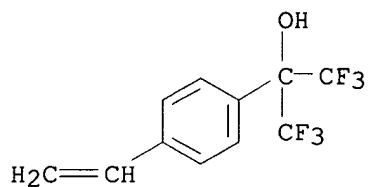
CMF C15 H19 F3 O2



CM 2

CRN 2386-82-5

CMF C11 H8 F6 O



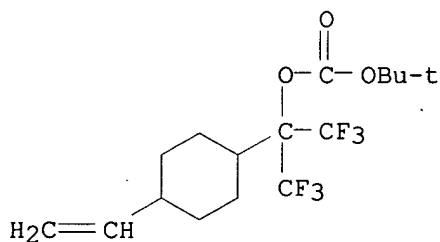
RN 607710-76-9 HCAPLUS

CN Carbonic acid, 1,1-dimethylethyl 1-(4-ethenylcyclohexyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)cyclohexanemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 607710-75-8

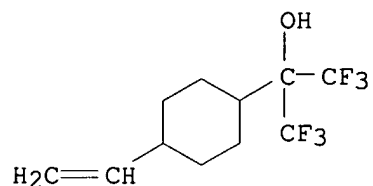
CMF C16 H22 F6 O3



CM 2

CRN 607710-74-7

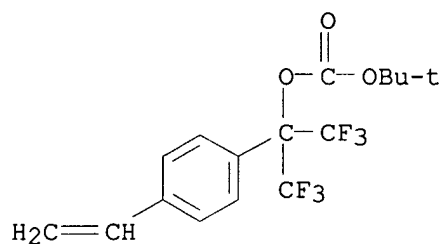
CMF C11 H14 F6 O



RN 607710-77-0 HCAPLUS
 CN Carbonic acid, 1,1-dimethylethyl 1-(4-ethenylphenyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene and 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

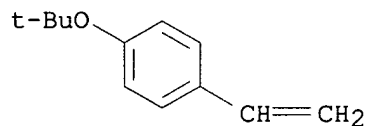
CM 1

CRN 143336-93-0
 CMF C16 H16 F6 O3



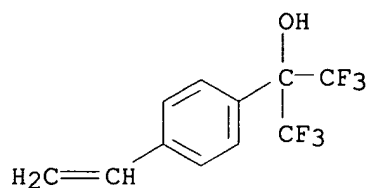
CM 2

CRN 95418-58-9
 CMF C12 H16 O



CM 3

CRN 2386-82-5
 CMF C11 H8 F6 O



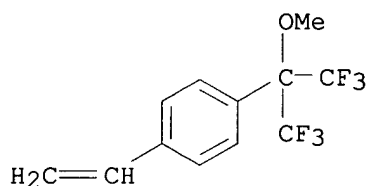
RN 607710-78-1 HCAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 1-ethenyl-4-[2,2,2-trifluoro-1-methoxy-1-(trifluoromethyl)ethyl]benzene (9CI) (CA INDEX NAME)

CM 1

CRN 483348-89-6

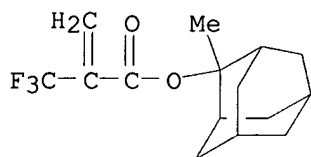
CMF C12 H10 F6 O



CM 2

CRN 188739-86-8

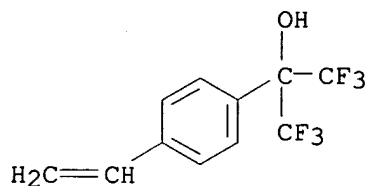
CMF C15 H19 F3 O2



CM 3

CRN 2386-82-5

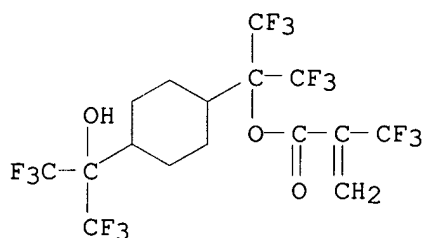
CMF C11 H8 F6 O



RN 610300-97-5 HCAPLUS
 CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl ester, polymer with 5-[2-(ethoxymethoxy)-3,3,3-trifluoro-2-(trifluoromethyl)propyl]bicyclo[2.2.1]hept-2-ene (9CI) (CA INDEX NAME)

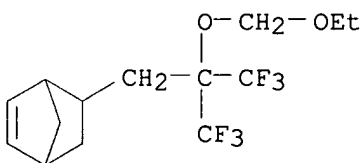
CM 1

CRN 479072-83-8
 CMF C16 H13 F15 O3



CM 2

CRN 328114-61-0
 CMF C14 H18 F6 O2

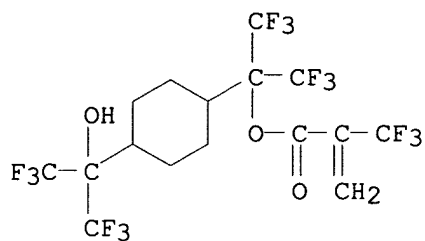


RN 610300-98-6 HCAPLUS
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 479072-83-8

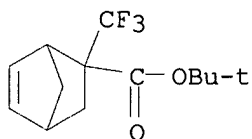
CMF C16 H13 F15 O3



CM 2

CRN 365568-55-4

CMF C13 H17 F3 O2



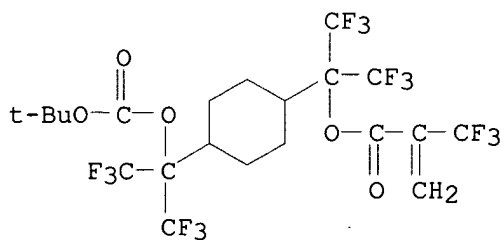
RN 610301-00-3 HCAPLUS

CM 2-Propenoic acid, 2-(trifluoromethyl)-, 1-[4-[1-[[1,1-dimethylethoxy)carbonyl]oxy]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]cyclohexyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with tricyclo[3.3.1.13,7]dec-1-yl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 610300-99-7

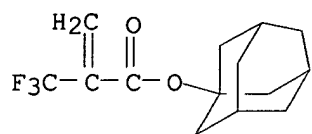
CMF C21 H21 F15 O5



CM 2

CRN 188739-82-4

CMF C14 H17 F3 O2



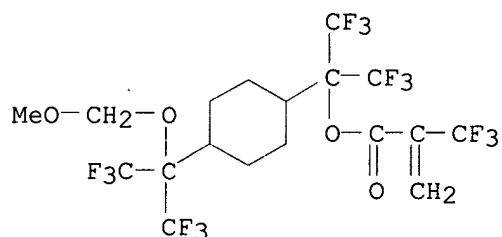
RN 610301-03-6 HCAPLUS

CM Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(trifluoromethyl)-, methyl ester, polymer with 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-(methoxymethoxy)-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 610301-02-5

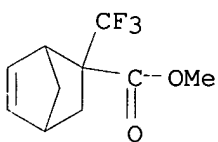
CMF C18 H17 F15 O4



CM 2

CRN 597581-42-5

CMF C10 H11 F3 O2



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